

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L16	19	L14 and mixing	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 15:02
L15	31	L14 and mix\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 15:02
L14	81	L12 and pressure	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 15:02
L13	81	L12 and pressure	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 15:02
L12	259	muraoka adj yusuke. in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 15:02
L11	11	L10 and "134".clas.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 15:02
L10	37	((fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (horizontal\$4 or side or lateral or swirl\$3 or spin\$4 or flowing) with (spray \$3 or nozzle or discharg\$3 or dispos \$3) same (chamber or tank) same (hold \$3 or plate) same (substrate or semiconductor or wafer or semi \$1conductor) same	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 15:02

		(rotat\$3 or spin\$4)				
L9	1162	134/200	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 15:02
L7	3	"6306564".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 14:39
L6	27	(fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (horizontal\$4 or side or lateral or swirl\$3 or angled or angling or angle) with (spray \$3 or nozzle or discharg\$3 or dispos \$3) same (chamber or tank) same (hold \$3 or plate) same (substrate or semiconductor or wafer or semi \$1conductor) same (rotat\$3 or spin\$4 or rotary)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 14:39
L5	37	(fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (horizontal\$4 or side or lateral or swirl\$3 or spin\$4 or flowing) with (spray \$3 or nozzle or discharg\$3 or dispos \$3) same (chamber or tank) same (hold \$3 or plate) same (substrate or semiconductor or wafer or semi \$1conductor) same	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 14:27

		(rotat\$3 or spin\$4 or rotary)				
L4	164	(fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (spray\$3 or nozzle or discharg\$3 or dispos\$3) same (chamber or tank) same (hold\$3 or plate) same (substrate or semiconductor or wafer or semi \$1conductor) same (rotat\$3 or spin\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 14:27
L3	691	(substrate or semiconductor or wafer or semi \$1conductor) same (rotat\$3 or spin\$4) and (fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (spray\$3 or nozzle or discharg\$3 or dispos\$3) same (chamber or tank) same (hold\$3 or plate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 14:27
L2	1253	(substrate or semiconductor or wafer or semi \$1conductor) same (rotat\$3 or spin\$4) and (fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (spray\$3 or nozzle or discharg\$3 or	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 14:26

		dispos\$3) and (chamber or tank) same (hold\$3 or plate)				
L1	3440	(substrate or semiconductor or wafer or semi \$1conductor) same (rotat\$3 or spin\$4) and (fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (spray\$3 or nozzle or discharg\$3 or dispos\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/11/05 14:26

11/5/2008 3:06:07 PM

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